

## Chapter 18: Electrical Properties

### ISSUES TO ADDRESS...

- How are electrical conductance and resistance characterized?
- What are the physical phenomena that distinguish \_\_\_\_\_?
- For metals, how is \_\_\_\_\_ affected by \_\_\_\_\_ and deformation?
- For semiconductors, how is conductivity affected by impurities (doping) and temperature?

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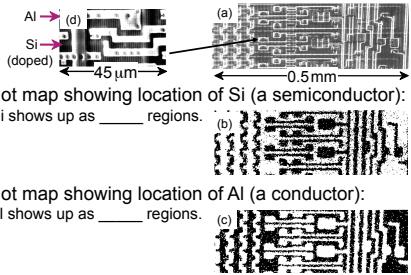
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## View of an Integrated Circuit

- Scanning \_\_\_\_\_ micrographs of an IC:

Fig. (d) from Fig. 12-27(a), Callister & Rethwisch 3e.  
(Figs. 12-27 is courtesy Nick Gonzales, National Semiconductor Corp., West Jordan, UT.)

Figs. (a), (b), (c) from Fig. 18-27, Callister &amp; Rethwisch 8e.

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## Electrical Conduction

- \_\_\_\_\_ Law:  
voltage drop (volts = J/C)  $V = IR$  resistance (Ohms)  
 $C = \underline{\hspace{2cm}}$  current (amps = C/s)
- \_\_\_\_\_,  $\rho$ :  
– a material property that is independent of sample size and geometry  
 $\rho = \frac{RA}{l}$  surface area of current flow  
current flow path length
- \_\_\_\_\_,  $\sigma$

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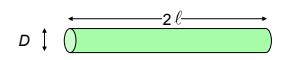
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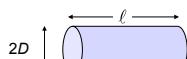
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## Electrical Properties

- Which will have the greater \_\_\_\_\_?



$$R_1 = \frac{2\rho\ell}{\pi\left(\frac{D}{2}\right)^2} = \frac{8\rho\ell}{\pi D^2}$$



$$R_2 = \frac{\rho\ell}{\pi \left(\frac{2D}{2}\right)^2} = \frac{\rho\ell}{\pi D^2} = \frac{R_1}{8}$$

- Analogous to flow of water in a pipe
  - \_\_\_\_\_ depends on sample geometry and size.

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## Definitions

## Further definitions

$$J = \frac{\text{current}}{\text{surface area}} = \frac{I}{A} \quad \text{like a flux}$$

$$\varepsilon \equiv \underline{\hspace{1cm}}$$

$$J = \sigma(V\ell)$$

## Electron flux conductivity

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## Conductivity: Comparison

- Room temperature values  $(\text{Ohm}\cdot\text{m})^{-1} = (\Omega \cdot \text{m})^{-1}$

METALS	conductors	
Silver	$6.8 \times 10^7$	Soda-lime glass
Copper	$6.0 \times 10^7$	Concrete
Iron	$1.0 \times 10^7$	Aluminum oxide

Silicon	$4 \times 10^{-4}$
Germanium	$2 \times 10^0$
GaAs	$10^{-6}$

semiconductors

POLYMERS	
Polystyrene	$<10^{-14}$
Polyethylene	$10^{-15}$ - $10^{-17}$

Selected values from Tables 18.1, 18.3, and 18.4, Callister & Rethwisch 8e.

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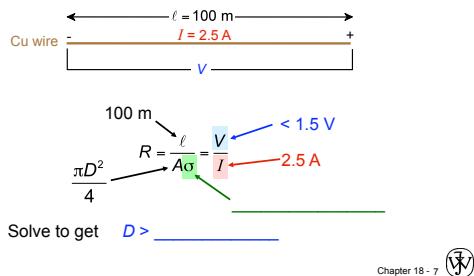
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### Example: Conductivity Problem

What is the minimum diameter ( $D$ ) of the wire so that  $V < 1.5$  V?



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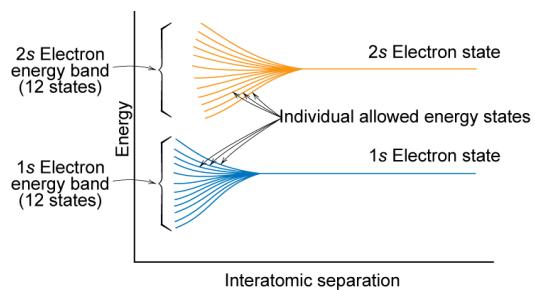
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### Electron Energy Band Structures



Adapted from Fig. 18.2, Callister & Rethwisch 8e.

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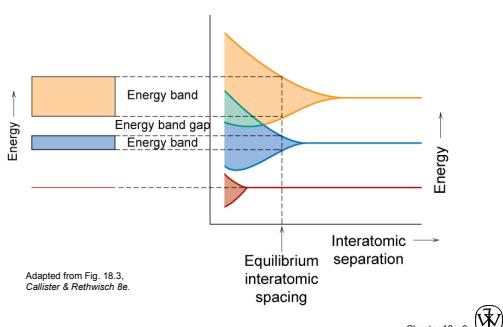
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### Band Structure Representation



Adapted from Fig. 18.3,  
Callister & Rethwisch 8e.

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### Conduction & Electron Transport

- Metals (\_\_\_\_\_):
  - for metals \_\_\_\_\_ are adjacent to filled states.
  - thermal energy excites \_\_\_\_\_ into empty higher energy states.
  - two types of band structures for metals
    - empty band that overlaps filled band

The diagram illustrates two types of band structures for metals. On the left, a 'Partially filled band' shows a gap between the filled valence band (bottom) and an empty conduction band (top). Electrons can move from the valence band to the conduction band upon excitation. On the right, 'Overlapping bands' show a situation where an empty band overlaps with a filled band. Electrons from the filled band can move into the empty band upon excitation. Both diagrams include arrows indicating electron movement and labels for 'empty band', 'filled states', 'filled band', and 'GAP'.

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### Energy Band Structures: Insulators & Semiconductors

- \_\_\_\_\_:
  - wide band gap (\_\_\_\_ eV)
  - few electrons excited across band gap
- \_\_\_\_\_:
  - narrow band gap (\_\_\_\_ eV)
  - more electrons excited across band gap

The diagram compares insulator and semiconductor band structures. The left panel for an insulator shows a wide band gap between the filled valence band and the empty conduction band. A small number of electrons (indicated by arrows) are excited across the gap. The right panel for a semiconductor shows a narrower band gap. A larger number of electrons are excited across the gap, filling some states in the conduction band. Both panels include labels for 'empty conduction band', 'GAP', 'filled valence band', 'filled states', and 'filled band'.

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### Metals: Influence of Temperature and Impurities on Resistivity

- \_\_\_\_\_ increases resistivity
  - grain boundaries
  - \_\_\_\_\_
  - impurity atoms

These act to scatter electrons so that they take a less direct path.

A graph showing Resistivity ( $\rho$ ,  $10^{-8}$  Ohm-m) versus Temperature ( $T$ , °C). Four curves are plotted: 'Pure Cu' (red), 'Cu + 1.12 at%Ni' (blue), 'deformed Cu + 1.12 at%Ni' (green), and 'Cu + 3.32 at%Ni' (dark green). All curves show an increase in resistivity with temperature. The 'Pure Cu' curve has the lowest resistivity, while the 'Cu + 3.32 at%Ni' curve has the highest.

Adapted from Fig. 18.8. Callister & Rethwisch 8e. (Fig. 18.8 adapted from J.O. Linde, Ann. Physik 9, p. 219 (1932); and C.A. Wert and R.M. Thomson, Physics of Solids, 2nd ed., McGraw-Hill Book Company, New York, 1970.)

Resistivity,  $\rho$   
( $10^{-8}$  Ohm-m)

Temperature,  $T$  (°C)

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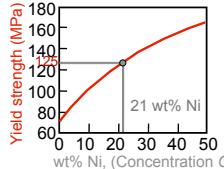
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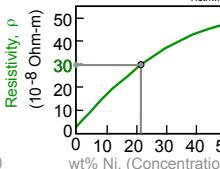
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### Estimating Conductivity

• Question:  
-- Estimate the electrical conductivity  $\sigma$  of a Cu-Ni alloy that has a yield strength of 125 MPa.



Adapted from Fig. 7.16(b), Callister & Rethwisch 8e.



Adapted from Fig. 18.9, Callister & Rethwisch 8e.

From step 1:  
 $C_{Ni} = \underline{\hspace{2cm}} \text{ Ni}$

$$\sigma = \frac{1}{\rho} = 3.3 \times 10^6 (\text{Ohm} \cdot \text{m})^{-1}$$

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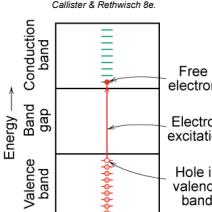
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### Charge Carriers in Insulators and Semiconductors

Adapted from Fig. 18.6(b), Callister & Rethwisch 8e.



Two        carriers:

- charge  
-        charge in conduction band
- charge  
-        charge - vacant electron state in the valence band

Move at different speeds - drift velocities

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### Intrinsic Semiconductors

- Pure material                 : e.g., silicon & germanium
  - Group IVA materials
- Compound semiconductors
  - compounds
    - Ex: GaAs & InSb
  - compounds
    - Ex: CdS & ZnTe
- The wider the electronegativity difference between the elements the wider the energy gap.

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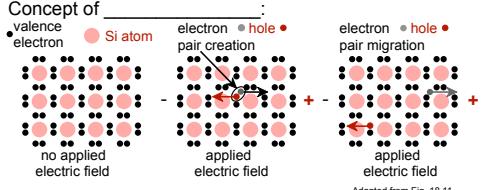
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### Intrinsic Semiconduction in Terms of Migration

- Concept of \_\_\_\_\_:  


Si atom electron hole pair creation electron hole pair migration

no applied electric field applied electric field applied electric field
- Electrical \_\_\_\_\_ given by:  

$$\sigma = n|e|\mu_e + p|e|\mu_h$$

# holes/m<sup>3</sup> # electrons/m<sup>3</sup> electron mobility hole mobility

Adapted from Fig. 18.11, Callister & Rethwisch 8e.

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### Number of Charge Carriers

Conductivity

$$\sigma = n|e|\mu_e + p|e|\mu_h$$

- for \_\_\_\_\_ semiconductor  $n = p = n_i$   
 $\therefore \sigma = n_i|e|(\mu_e + \mu_h)$
- Ex: GaAs  

$$n_i = \frac{\sigma}{|e|(\mu_e + \mu_h)} = \frac{10^{-6}(\Omega \cdot m)^{-1}}{(1.6 \times 10^{-19} C)(0.85 + 0.45 m^2/V \cdot s)}$$

For GaAs  $n_i = \underline{\hspace{2cm}}$   
 For Si  $n_i = 1.3 \times 10^{16} \text{ m}^{-3}$

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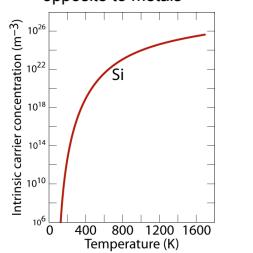
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### Intrinsic Semiconductors: Conductivity vs T

- Data for \_\_\_\_\_:  
 $\sigma$  increases with  $T$   
 $\sigma$  opposite to metals



Intrinsic carrier concentration ( $\text{m}^{-3}$ )

Temperature (K)

Si

$n_i \propto e^{-E_{gap}/kT}$

material	band gap (eV)
Si	1.11
Ge	0.67
GaP	2.25
CdS	2.40

Selected values from Table 18.3, Callister & Rethwisch 8e.

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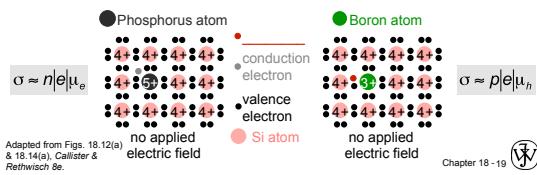
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### Intrinsic vs Extrinsic Conduction

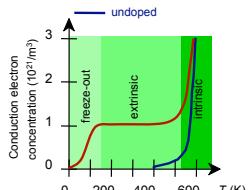
- \_\_\_\_\_:
  - case for pure Si
  - # electrons = # \_\_\_\_\_ ( $n = p$ )
- \_\_\_\_\_:
  - electrical behavior is determined by presence of impurities that introduce excess electrons or holes
- \_\_\_\_\_
- ***n-type*** \_\_\_\_\_: ( $n \gg p$ ) • ***p-type*** Extrinsic: ( $p \gg n$ )



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### Extrinsic Semiconductors: Conductivity vs. Temperature

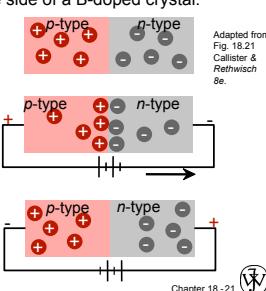
- Data for \_\_\_\_\_:
  - \_\_\_\_\_
  - reason: imperfection sites lower the activation energy to produce mobile electrons.
- Comparison: \_\_\_\_\_ vs extrinsic conduction...
  - \_\_\_\_\_ doping level:  $10^{21}/m^3$  of a *n*-type donor impurity (such as P).
  - for  $T < 100$  K: "freeze-out", thermal energy insufficient to excite electrons.
  - for  $150$  K  $< T < 450$  K: "extrinsic"
  - for  $T \gg 450$  K: "intrinsic"



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### p-n Rectifying Junction

- Allows flow of \_\_\_\_\_ in one direction only (e.g., useful to convert \_\_\_\_\_ current to \_\_\_\_\_ current).
- Processing: diffuse P into one side of a B-doped crystal.
- No applied \_\_\_\_\_:
  - \_\_\_\_\_
- \_\_\_\_\_ bias: carriers flow through *p*-type and *n*-type regions; holes and electrons recombine at *p-n* junction; current flows.
- \_\_\_\_\_ bias: carriers flow away from *p-n* junction; junction region depleted of carriers; little current flow.



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### Properties of Rectifying Junction

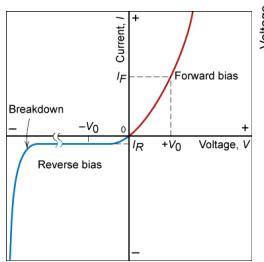


Fig. 18.22. Callister &amp; Rethwisch 8e.

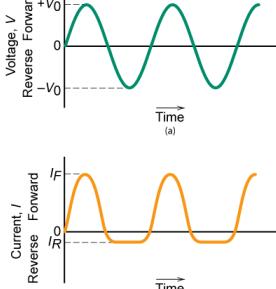


Fig. 18.23. Callister &amp; Rethwisch 8e.

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### Junction Transistor

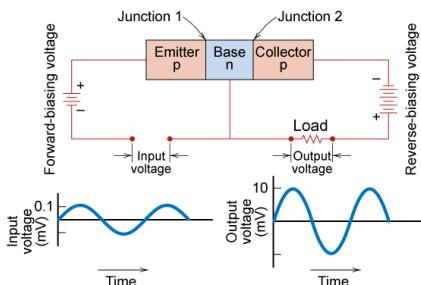


Fig. 18.24. Callister &amp; Rethwisch 8e.

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### MOSFET Transistor Integrated Circuit Device

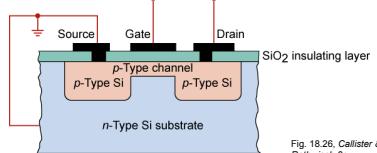


Fig. 18.26. Callister &amp; Rethwisch 8e.

- MOSFET (\_\_\_\_\_)
- Integrated circuits - state of the art ca. \_\_\_\_ nm line width
  - ~ 1,000,000,000 components on chip
  - chips formed one layer at a time

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## Ferroelectric Ceramics

- Experience \_\_\_\_\_ polarization

$\text{BaTiO}_3$  -- ferroelectric below its \_\_\_\_\_ temperature ( $120^\circ\text{C}$ )

Fig. 18.35, Callister & Rethwisch 8e.

(a)

(b)

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## Piezoelectric Materials

- application of stress induces \_\_\_\_\_
- application of voltage induces dimensional change

stress-free

with applied stress

σ

σ

Adapted from Fig. 18.36, Callister & Rethwisch 8e. (Fig. 18.36 from Van Vlack, Lawrence H., Elements of Materials Science and Engineering, 1989, p.482. Adapted by permission of Pearson Education, Inc., Upper Saddle River, New Jersey.)

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## Summary

- Electrical **conductivity** and **resistivity** are:
  - material parameters
  - geometry independent
- Conductors, semiconductors, and insulators...
  - differ in range of conductivity values
  - differ in availability of electron excitation states
- For metals, **resistivity** is increased by
  - increasing temperature
  - addition of imperfections
  - plastic deformation
- For pure semiconductors, **conductivity** is increased by
  - increasing temperature
  - doping [e.g., adding B to Si (*p*-type) or P to Si (*n*-type)]
- Other electrical characteristics
  - ferroelectricity
  - piezoelectricity

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